

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	63665	(clean or preclean or etch or remov) same (oxide or dioxide)	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	OR	ON	2005/08/16 11:03
L2	1321214	(clean or preclean or etch or remov) same sulfuric acid	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	OR	ON	2005/08/16 11:04
L3	26165	(clean or preclean or etch or remov) same sulfuric acid same hf	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	OR	ON	2005/08/16 11:06
L4	442697	(clean or preclean or etch or remov)	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	OR	ON	2005/08/16 11:07
L5	235307	sulfuric acid same clean	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	OR	ON	2005/08/16 11:08
L6	227043	sulfuric acid same clean same remov\$	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	OR	ON	2005/08/16 11:14
L7	192	(438/8).CCLS.	USPAT; USOCR	OR	OFF	2005/08/16 11:32
L8	382	(438/756).CCLS.	USPAT; USOCR	OR	OFF	2005/08/16 13:44
L9	1785	(438/692).CCLS.	USPAT; USOCR	OR	OFF	2005/08/16 13:49
L10	576	(438/719).CCLS.	USPAT; USOCR	OR	OFF	2005/08/16 13:51
L11	125	(438/749).CCLS.	USPAT; USOCR	OR	OFF	2005/08/16 13:51
S3	45388	(epitax\$)	USPAT	OR	OFF	2005/08/16 09:14
S10	2	438/299-304	USPAT	OR	OFF	2005/08/02 17:40
S11	26569	oxide same acid same remov\$	USPAT	OR	OFF	2005/08/05 15:59
S12	62934	(clean or preclean) same surface	USPAT	OR	OFF	2005/08/05 15:59
S13	2332	S11 and S12	USPAT	OR	OFF	2005/08/05 16:00
S14	55638	gate same oxide	USPAT	OR	OFF	2005/08/05 16:00
S15	615	S13 and S14	USPAT	OR	OFF	2005/08/05 16:02
S16	6686	oxide and gate and clean	USPAT	OR	OFF	2005/08/05 16:03
S17	1891048	remov\$	USPAT	OR	OFF	2005/08/05 16:03
S18	108999	oxide same remov\$	USPAT	OR	OFF	2005/08/05 16:04

S19	3853	S16 and S18	USPAT	OR	OFF	2005/08/05 16:22
S20	17893	gate same oxide same remov\$	USPAT	OR	OFF	2005/08/05 16:41
S21	11174	silicon same oxide same gate same remov\$	USPAT	OR	OFF	2005/08/05 17:15
S22	430	(438/300).CCLS.	USPAT; USOCR	OR	OFF	2005/08/08 10:02
S26	0	("l12and(cleanorpreclean)").PN.	USPAT; USOCR	OR	OFF	2005/08/05 17:19
S27	96	S22 and (pre\$1clean\$3 clean\$3)	USPAT	OR	OFF	2005/08/08 08:34
S28	1	("4998150").PN.	USPAT; USOCR	OR	OFF	2005/08/08 08:02
S29	14963	oxide same silicon same acid	USPAT	OR	OFF	2005/08/08 08:35
S30	2021	oxide same silicon same acid same gate	USPAT	OR	OFF	2005/08/08 08:50
S31	124978	oxide same silicon	USPAT	OR	OFF	2005/08/08 09:04
S32	49388	S31 and gate	USPAT	OR	OFF	2005/08/08 09:05
S33	65058	"438"/\$4	USPAT	OR	OFF	2005/08/08 09:27
S34	135	(438/225).CCLS.	USPAT; USOCR	OR	OFF	2005/08/08 10:02
S35	13346	(epitax\$)same oxide	USPAT	OR	OFF	2005/08/08 13:39
S36	941	(epitax\$)same oxide same clean\$3	USPAT	OR	OFF	2005/08/12 12:03
S37	78	(438/222).CCLS.	USPAT; USOCR	OR	OFF	2005/08/08 14:54
S38	1084	(epitax\$) same clean	USPAT	OR	OFF	2005/08/09 10:57
S39	135	(117/43).CCLS.	USPAT; USOCR	OR	OFF	2005/08/09 12:25
S40	676399	oxidant acid	USPAT	OR	OFF	2005/08/09 13:18
S41	2810245	surface cleanning process	USPAT	OR	OFF	2005/08/09 13:07
S42	604866	S40 and S41	USPAT	OR	OFF	2005/08/09 12:31
S43	272420	S42 and oxide	USPAT	OR	OFF	2005/08/09 12:23
S44	272420	S41 and S43	USPAT	OR	OFF	2005/08/09 11:51
S52	122356	S40 and S41 and silicon	USPAT	OR	OFF	2005/08/09 12:33
S53	10847	S40 and S41 and silicon same gate	USPAT	OR	OFF	2005/08/09 12:34
S54	2107427	surface cleanning process same silicon same oxide	USPAT	OR	OFF	2005/08/09 13:00
S55	1	surface same cleanning same oxide	USPAT	OR	OFF	2005/08/09 13:09
S56	1681	clean same oxide same acid	USPAT	OR	OFF	2005/08/09 13:36
S57	1	("6878575").PN.	USPAT; USOCR	OR	OFF	2005/08/09 14:48
S58	1	("6884701").PN.	USPAT; USOCR	OR	OFF	2005/08/09 14:48
S59	29787	implant\$ same oxide	USPAT	OR	OFF	2005/08/12 08:58